

<b>Notice of References Cited</b>		Application/Control No.	Applicant(s)/Patent Under Reexamination	
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		Examiner	Art Unit	Page 1 of 1
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	B	US-5,929,980	07-1999	Yamaguchi et al.	356/4.03
	C	US-5,946,092	08-1999	DeFreez et al.	356/336
	D	US-6,366,690	04-2002	Smilansky et al.	382/149
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	N	10-232196 <sub>c</sub>	09-1998	JP	Ito et al.	
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**NON-PATENT DOCUMENTS**

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	U	Uesugi et al., "Real-time monitoring of scattered laser light by a single particle of several tens of nanometers in the etching chamber in relation to its status with the equipment," J Vac Sci Techn. A 16(3), May/June 1998, pg. 1189-1195.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.